

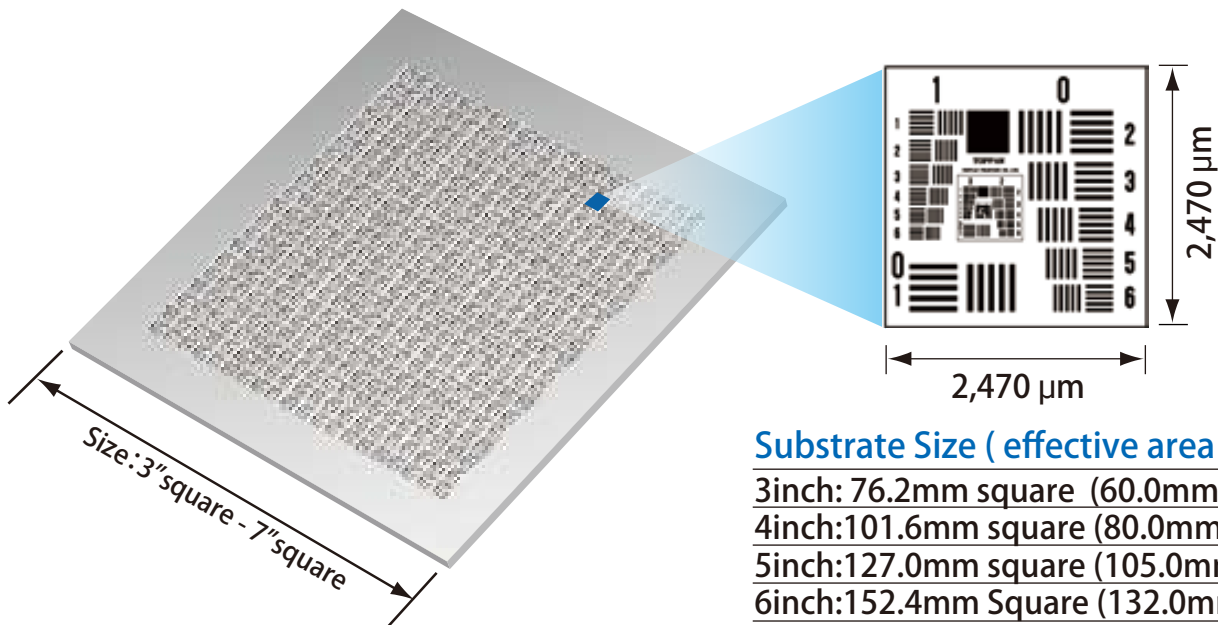
For precision management, the resolution confirmation of the device

TOPPAN TEST CHART

It is the photomask which formed the basic-shaped pattern with chromium on the high purity glass substrate.

We prepare for a positive type mask and a negative type mask.

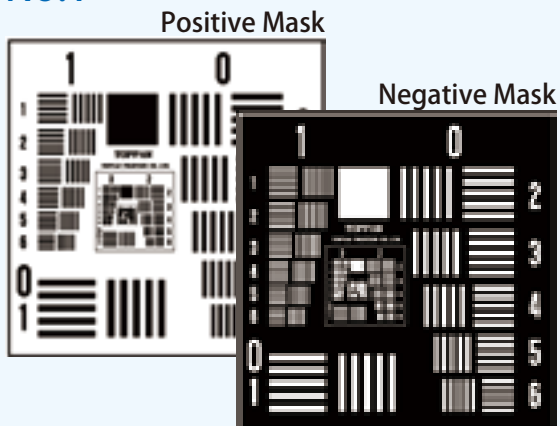
It is available in the uses such as accuracy management of equipment, a resolution check, and a valuation basis at photoresist selection.



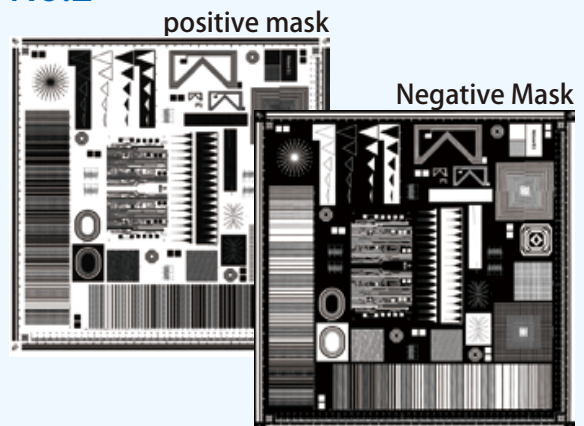
Substrate Size (effective area)

3inch:	76.2mm square (60.0mm square)
4inch:	101.6mm square (80.0mm square)
5inch:	127.0mm square (105.0mm square)
6inch:	152.4mm Square (132.0mm square)
7inch:	177.8mm Square (145.0mm square)

No.1



No.2



In addition to the above standard products, we can also produce custom models.